

AR-P 5350 – run sheet

Allresist

nanyte.com/photoresists/ar-p-5350 · last updated 2026-07-26

Thickness: 1 μm

Softbake: 105 °C · 4 min · hotplate

Exposure dose: 55 mJ/cm²

Develop: Developer AR 300-35 (primary, fully worked example); AR 300-26 or AR 300-47 listed as alternatives · Dilution AR 300-35 at 1:2 (worked example); alternatively AR 300-26 at 1:7, or AR 300-47 at 2:3 – per the 'Development recommendations' table, AR-P 5350 row · Time 60 s · Rinse DI-H₂O, 30 s · Method puddle